



Session Title:	[TuF2] Nano Thin Film Deposition II
Session Date:	November 12 (Tue.), 2024
Session Time:	14:55-16:30
Session Room:	Room F (Ballroom, 5F, Grand Josun Busan)
Session Chair:	Prof. Satoshi Hamaguchi (Osaka Univ., Japan)

[TuF2-1] [Invited]

14:55-15:25

The Challenges and the Future of Thin Film Technology in the New Era of Paradigm Shift

Jinhee Park and Dongwon Choi (SK hynix Inc., Korea)

[TuF2-2] [Invited]

15:25-15:50

Recent Development of Area-Selective Atomic Layer Deposition for Electronic Devices

Il-Kwon Oh (Ajou Univ., Korea)

[TuF2-3]

15:50-16:10

Development of Warpage Control Technique for High-STACK 3D NAND Flash Memory Device

Sangyeop Lee, Jeong Jun Lee, Ji Min Seo, Ah Yeong Choi, Yudeuk Kim, and Jaegab Lim
(Wonik IPS, Korea)

[TuF2-4]

16:10-16:30

Low Temperature Flow Modulation (FM)-CVD for High Thermal Conductivity AlN Film
Formation for Advanced 3DICs

Y. Otaka, J. Yamaguchi, N. Sato, A. Tsukune, and Y. Shimogaki (The Univ. of Tokyo, Japan)